

Lecture 3

Building Blocks of Integrated Circuits

March 9, 2005

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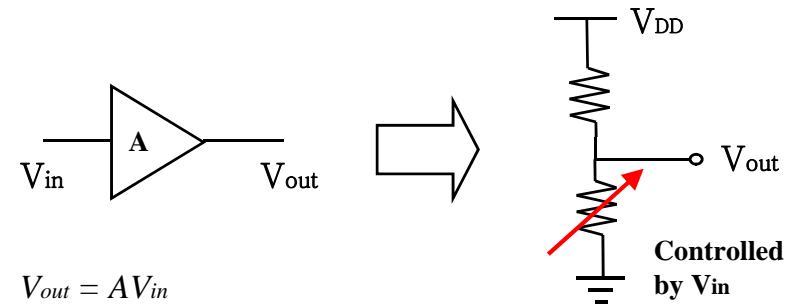
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How to design a gain element

When we are going to design amplifiers for a varying gain,
what is the simplest way?



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Outline

Transistor

Semiconductor fundamentals

MOS Transistor

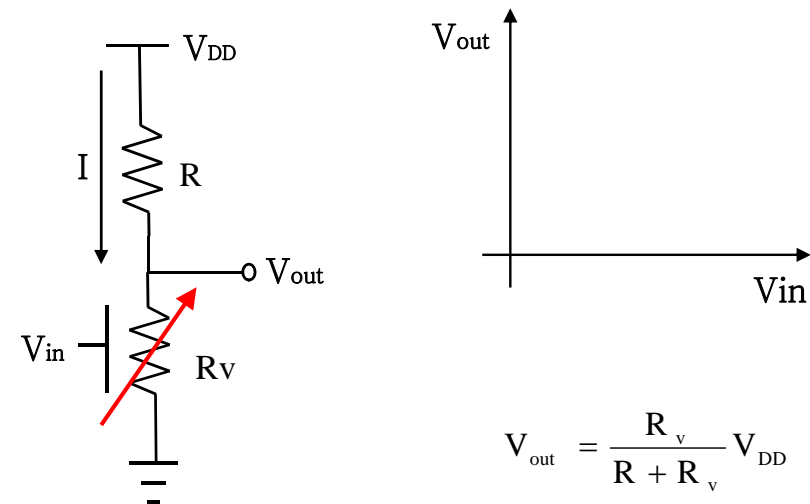
BJT

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Variable Resistor

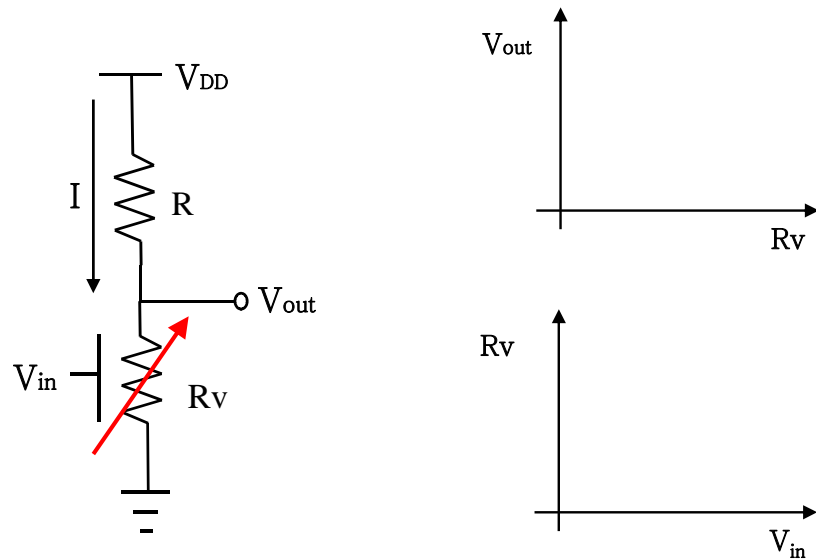


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Variable Resistor



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How to design a gain element

By similar approach, we can also derive an exponential relation between V_{in} and V_{out} . In this case, you can see the characteristic of BJT.

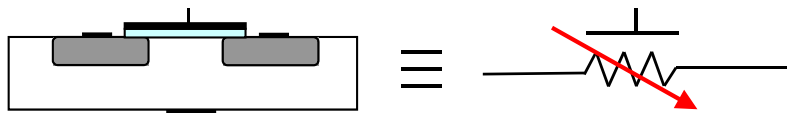
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Meaning of Transistor

$$R_v \propto \frac{1}{V_{in}}$$

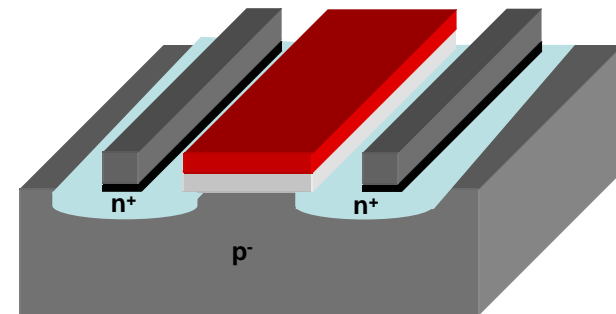


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Structure of MOS Transistor



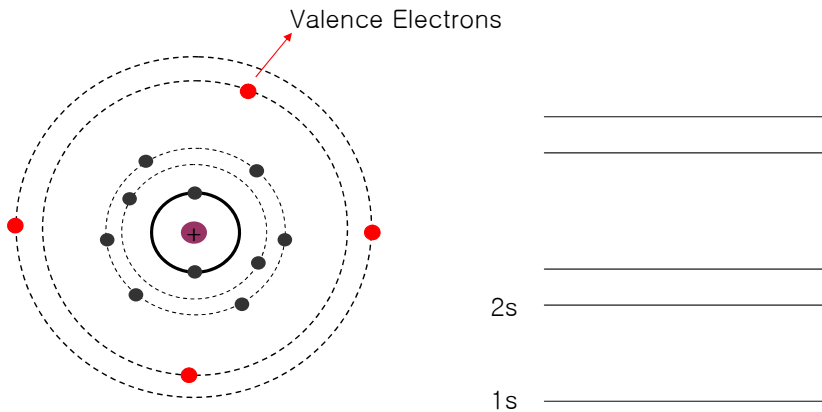
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Fundamentals of Semiconductor

- Si : 14 \rightarrow $1s^2 2s^2 2p^6 3s^2 3p^2$

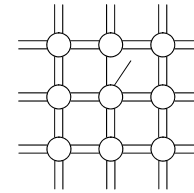


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Energy Bands



Conduction

Valence

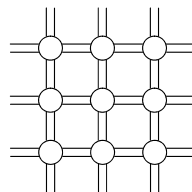
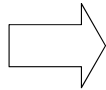
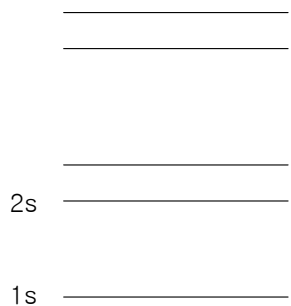
Electron – hole pair

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Si in Crystal



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Energy Bands of Different Materials

	Insulator	Semi-conductor	Conductor
Energy-band			
Free Electrons:			

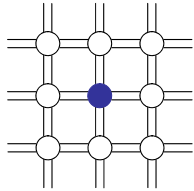
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Adding Impurities

At room temperature, $n_i \approx 10^{10} / \text{cm}^3$, # of atoms = $10^{22} / \text{cm}^3$
 → one out of _____ atoms is ionized at room temperature.



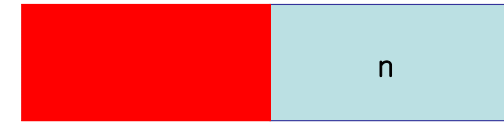
p, p+, p-
 n, n+, n-

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P-N Junction



Diffusion :

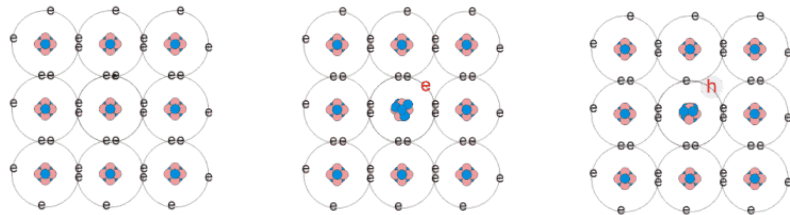
Drift:

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Doped semiconductors

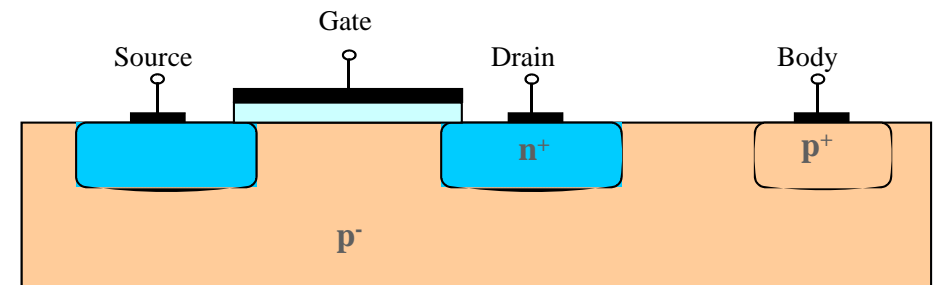


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Operation of MOS Transistor



Linear Region:
$$I_D = \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_T) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

Saturated Region:
$$I_D = \frac{1}{2} \mu_n C_{ox} \frac{W}{L} \left[(V_{GS} - V_T) V_{DS} - \frac{1}{2} V_{DS}^2 \right]$$

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Intuitive Understanding of I-V

$$I = v \cdot Q$$

$$Q = CV$$

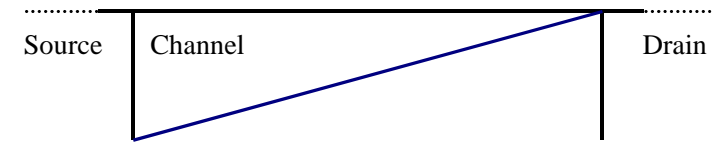
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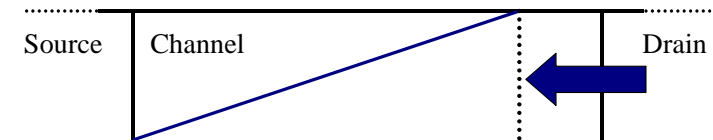
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2nd order Effect : Channel Length Mod.

4. Operation as V_{DS} is increased beyond V_{DSsat}



Channel length modulation occurs,



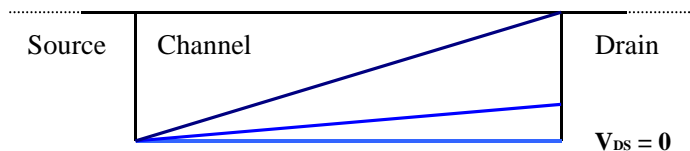
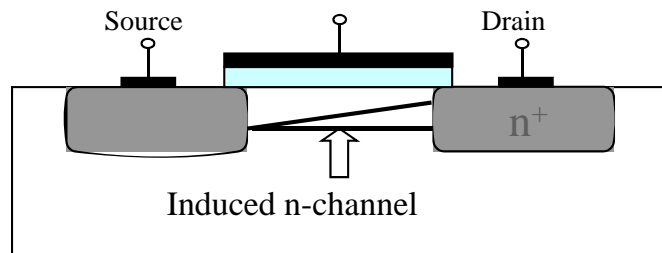
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Operation of MOS Transistor

3. Operation as V_{DS} is increased



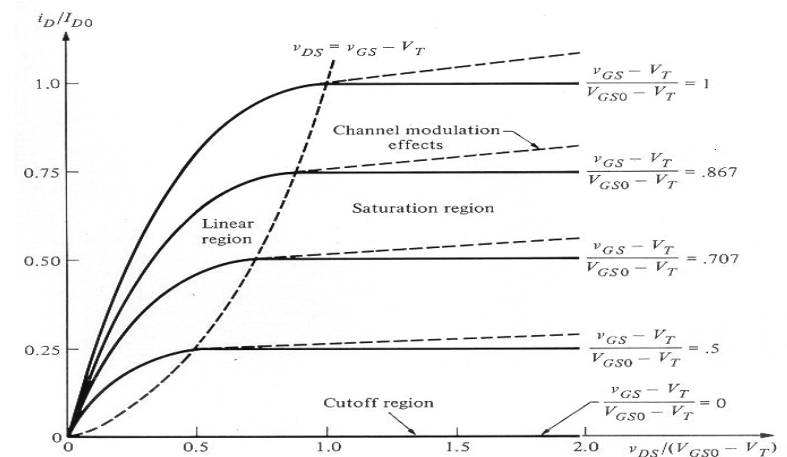
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Operation of MOS Transistor

$$i_D = \frac{1}{2} K_n \frac{W}{L} (V_{GS} - V_T)^2 (1 + \lambda V_{DS})$$

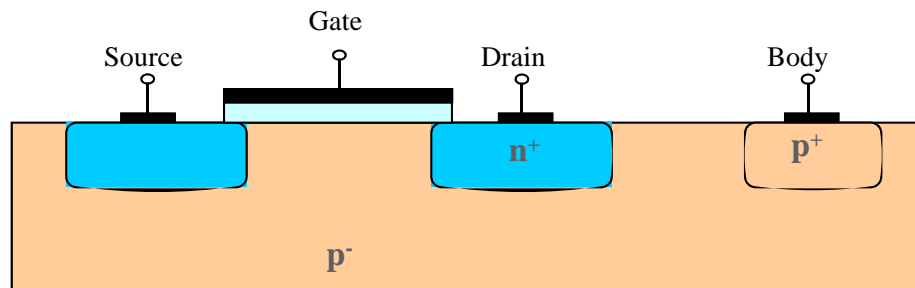


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2nd Order Effects: Body Effect



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Comparison

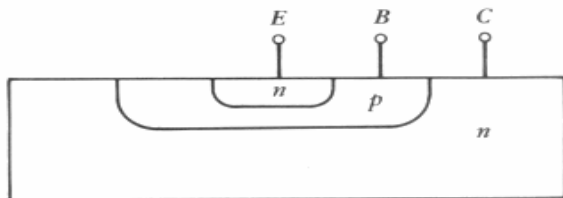
	MOS	BJT
Current flow	_____ carrier by _____	_____ carrier by _____
Model	_____ -controlled current source	_____ -controlled current source
I-V characteristics	Square	Exponential

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BJT Basics



Conduction mechanism in a bipolar transistor is made of the _____ **CARRIERS** flowing through the base region.

Currents are flowing through semiconductors junctions, within the crystalline structure. Not a surface effect.

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